Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	1624	(438/780).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO	OR	OFF	2005/05/11 15:52
L2	498	(438/781).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO	OR	OFF	2005/05/11 15:52
L3	602	(438/784).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO	OR	OFF	2005/05/11 15:52
L4	762	(438/787).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO	OR	OFF	2005/05/11 15:52
L5	544	(438/788).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO	OR	OFF	2005/05/11 15:52
L6	336	(438/789).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO	OR	OFF	2005/05/11 15:53
L7	382	(438/790).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO	OR	OFF	2005/05/11 15:53
L8	412	organosilicon and barrier adj layer	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/11 15:53
L9	26	l1 and l8	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/11 15:54
L10	13	l2 and l8	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/11 16:02

L11	2	I3 and I8	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/11 16:04
L12	9	I4 and I8	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/11 16:04
L13	10	I5 and I8	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/11 16:06
L14	33	I6 and I8	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/11 16:08
L15	24	I7 and I8	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/11 16:20
L16	21	organosilicon and (trimethylsilane or tetramethylcyclotetrasiloxane or octamethylcyclotetrasiloxane) and ((oxidizing adj gas with oxygen) or ozone or carbon or nitrous) and (initiation or seed) and barrier adj layer	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/11 16:23

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L4	21	organosilicon and ((initiat$4 or seed)adj layer) and barrier adj layer and ratio	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/11 12:14
L5	1	organosilicon and ((initiat$4 or seed)adj layer) and barrier adj layer and second near2 ratio	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/11 10:55
L6	1	organosilicon and ((initiat$4 or seed)adj layer) and second near2 ratio	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/11 10:58
L7	94	organosilicon and second near2 ratio	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/11 10:58
L8	72	organosilicon and second near2 ratio and silicon and carbon	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/11 11:10
L9	4	organosilicon and second adj ratio and silicon and carbon	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/11 11:42
L10	387	organosilicon and gas adj mixture and silicon and carbon	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/11 11:43
L11	18	organosilicon and (gas adj mixture with 1:1) and silicon and carbon	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/11 11:44

L12	0	organosilicon and (gas adj mixture with 10:1) and silicon and carbon	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/11 11:45
L13	0	organosilicon and (gas adj mixture with 20:1) and silicon and carbon	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/11 11:45
L14	0	organosilicon and (gas adj mixture with 50:1) and silicon and carbon	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/11 11:45
L15	4	organosilicon and (gas adj mixture with 100:1) and silicon and carbon	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/11 12:13
L16	447	(438/584).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO	OR	OFF	2005/05/11 12:13
L17	1083	(438/618).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO	OR	OFF	2005/05/11 12:13
L18	2369	(438/622).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO	OR	OFF	2005/05/11 12:13
L19	813	(438/629).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO	OR	OFF	2005/05/11 12:13
L20	2266	(438/637).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO	OR	OFF	2005/05/11 12:13
L21	799	(438/638).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO	OR	OFF	2005/05/11 12:13